Small Literature Survey of Recipes for DSSCs and ss-DSSCs

DSSCs with liquid electrolytes			Basic Dye Properties					Solar Cell Characterization											Electron transport															
																			anode							sintering		$TiCl_4$-treatment FTO (TiO_2)			
dye		reference	ε / $M^{-1}cm^{-1}$	at λ / nm	solvent	E_{HOMO} / eV	E_{LUMO} / eV	area / cm^2	Intensity	I_{SC} / (mA/cm^2)	U_{OC} / mV	FF	η / %	IPCE / %	at λ / nm	remaind η / %	at °C	after h	comment	TCO	Ω / sq	Cleaning procedure	e⁻ cond.	layer / µm	dense/nm	applicat.	particle size/nm	appl.	temp./°C	time/h	conc./mM	temp./°C	time/h	comment
Z907+HDMA	31	Wang2003							100 mW/cm²	15.2	764	0.676	**7.8**			>90	55	1000		FTO			TiO_2	10 (4)	-		20 (400)	SP	500	0.25	50 (40)	70	0.5	
Z907	31	Wang2003							100 mW/cm²	14.2	713	0.708	**7.2**							FTO			TiO_2	10 (4)	-		20 (400)	SP	500	0.25	50 (40)	70	0.5	
Z907	19	Kuang2008								13.9	731	0.69	**7.0**																					
K51	19	Kuang2008								14.8	730	0.715	**7.7**																					
K68	19	Kuang2008								14.4	762	0.69	**7.6**																					
K19	22	Nazeeruddin2007							100 mW/cm²	15.1	747	0.699	**8.0**							FTO		det.(15),H_2O,Et,UV-O_3(18	TiO_2	maybe 12(3)			20(400)		500	0.5	40 (40)	70	0.5	
N719	11	Ito2005	1.74E+04	535	Et.					16.6	778	0.731	**9.4**							FTO	10		TiO_2	14(4)	-		20(400)	SP			-			
N719	11	Ito2005	1.36E+04	535						17.6	805	0.738	**10.5**							FTO	10		TiO_2	14(4)	yes		20(400)	SP			-			
N719	11	Ito2005								18.7	798	0.713	**10.6**							FTO	10		TiO_2	14(4)	yes		20(400)	SP			40	70	0.5	
N719	22	Nazeeruddin2007							100 mW/cm²	15.82	785	0.75	**9.31**							FTO			TiO_2						500	0.5	40 (40)	70	0.5	
N719	2	Boschloo2006						0.785												FTO	8		TiO_2	13				CP	450	0.5				
N719	2	Boschloo2006						0.785			x + 260									FTO	8		TiO_2	13				CP	450	0.5				
N719	24	Saito2008							(100 mW/cm²)	18.11	621	0.585	**6.58**										ZnO	16.1 (6.7)			(20-30)							
N719	15	Karthikeyan2007				-5.9	-3.4																											
N719	20	Martinson2007						0.28	906 W/m²	3.3	739	0.64	**1.6**							AZO			ZnO	60			Al_2O_3 template	ALD	400	0.5	-			ALD-ZnO on Al_2O_3
N719	14	Kakiuchi2006							100 mW/cm²	12.6	668	0.481	**4.1**	60	460-550					ITO	4		ZnO	20			ca. 12		450	0.6				
N719	21	Mozer2008								11.68	775	0.72	**6.5**							FTO	10		TiO2	4.5			13		550	0.5	-			
N719	13	Jiang2006						0.14	100 mW/cm²	19	0.66	0.70	**8.9**	max. 80	540					FTO	10		TiO2	12 (4)			20 (400)		430 / 520	0.5	40			
N719	16	Koops2009							1 sun	9.55	670		3.82	APCE:78	467					FTO	15	Ac, Me, Hel.	TiO2	4	-			DB	450		-			
N719	23	O'Regan07						5x0.5cm												FTO	8		TiO_2	3			20	SP	570	10min	50	70	0.5	silver stripes
N3	9	Horiuchi2003	1.39E+04	541	AN:*t*-butan	-5.58		0.25	100 mW/cm²	16.77	698	0.54	**6.3**							FTO			TiO_2						550	2				
D102	9	Horiuchi2003	5.58E+04	491	AN:*t*-butan	-5.56		0.25	100 mW/cm²	17.76	604	0.57	**6.1**							FTO			TiO_2						550	2				
NKX-2311	9	Horiuchi2003				-5.54			100 mW/cm²	16.1	491	0.41	**3.3**							FTO			TiO_2											
D21L6	112	Yum2009	3.70E+04	458	Et.	0.98V vs.NHE	-1.35V vs.NHE		100.19 % sun	14.1	728	0.71	**7.25**			90	60	1000	stab. test in IL				TiO_2											
D5	8	Hagberg2008						0.2	100 mW/cm²	12	688	0.72	**5.94**	~ 85	~ 450-560					FTO			TiO_2	7 (5)	-		20 (400)	SP	500	0.5	yes (yes)			
D7	8	Hagberg2008						0.2	100 mW/cm²	11	695	0.71	**5.43**	~ 85	~ 450-550					FTO			TiO_2	7 (5)	-		20 (400)	SP	500	0.5	yes (yes)			
D9	8	Hagberg2008						0.2	100 mW/cm²	14	694	0.71	**6.9**	~ 85	~ 450-590					FTO			TiO_2	7 (5)	-		20 (400)	SP	500	0.5	yes (yes)			
D11	8	Hagberg2008						0.2	100 mW/cm²	13.5	744	0.7	**7.03**	~ 85	~ 450-590	90	60	1000		FTO			TiO_2	7 (5)	-		20 (400)	SP	500	0.5	yes (yes)			
D11	8	Hagberg2008						0.2	100 mW/cm²	12.3	765	0.7	**6.59**	79	~ 450-590					FTO			TiO_2	**2.5 (5)**	-		20 (400)	SP	500	0.5	yes (yes)			
D149	12	Ito2006	6.87E+04	526						19.96	653	0.694	**9.03**							FTO			TiO_2	12.6(4-5)	-		(400)	SP	500	0.5	40 (40)	70	0.5	
C201	32	Wang2008							100 mW/cm²	13.35	777	0.749	**7.8**	>80	~ 450 - 580					FTO			TiO_2	7(4)	-		20 (400)	SP						
(ZnPor)	4	Campbell2007																		FTO	15		TiO_2	10 (4)			20 (400)	SP	500	0.5				
DSSCs with ionic liquids:																																		
D21L6	33	Yum2009							1 sun	13.44	686	0.65	**5.98**										TiO_2											
C201	32	Wang2008							100 mW/cm²	12.4	723	0.779	**7**			6.2	60	1000	stability test wi	FTO			TiO_2	7(4)	-		20 (400)	SP						
ss-DSSCs with the solid hole transport material spiro-MeOTAD:																																		
N3	1	Bach1998			Et.				9.4 mW/cm²	0.32	342	0.62	**0.74**	33		80-120 %		80 h		FTO	10		TiO_2	4.2	yes	SPD		SP						
N719	17	Krüger2001						1.07	100 mW/cm²	5	910		**2.56**	~37	520	95%	RT	3 month		FTO	10		TiO_2	2.5	yes	SPD								
N719	18	Krüger2002						0.16		3.5	821	0.69	**2.1**																					
N719	18	Krüger2002						0.16		4.6	931	0.71	**3.2**																					
N719	6	Fabregat-Santiago2006						0.2					**1.0**										TiO_2	6	sev. tens		12		450	0.5				
Zn-1	25	Schmidt-Mende2005				-5.62	-3.46		100 mW/cm²	5.0	731	0.663	**2.44**	20 / 60	560-630/440					FTO	10		TiO_2	~ 2	<100	SPD	18	DB	450					
Zn-2	25	Schmidt-Mende2005				-5.52	-3.56		100 mW/cm²	5.9	790	0.651	**3.0**	25 / 65	570-650/440					FTO	10		TiO_2	~ 2	<100	SPD	18	DB	450					
D102	27	Schmidt-Mende2005b	5.58E+04					0.152	100 mW/cm²	7.7	866	0.612	**4.1**	~60	440-550			cheap dye		FTO			TiO_2	1.6	100	SPD	18		450		20			
Z907	26	Schmidt-Mende2005a							100 mW/cm²	8.3	752	0.64	**4.0**										TiO_2	2	yes	SPD		DB	450		-			
Z907	26	Schmidt-Mende2005a							100 mW/cm²	5.5	858	0.67	**3.1**										TiO_2	2	yes	SPD		DB	450		-			
Z907	**28**	**Schmidt-Mende2006**							**100 mW/cm²**	**8.32**	**752**	**0.643**	**4.03**							**FTO**		**Ac, Me, Hel.**	**TiO_2**	**2**	**100**	**SPD**	**19**	**DB**	**450**	**0.25**	**20**	**RT**	**o.n.**	
Z907	**7**	**Fabregat-Santiago2009**						**0.128**		**9.1**	**860**	**0.51**	**4**							**FTO**	**10**		**TiO_2**	**1.8**	**100**		**20**							
Z907	5	Ding2009																		FTO	15				100	SPD-O_2		SP	500 (450)	0.5	20 (20)	60	6	
K51	29	Snaith2006a						0.16												FTO	15	O_2-pl.(20)			100	SPD-O_2		DB	500	0.5	20	RT	6	
K68	30	Snaith2008																		FTO	15		TiO_2		100	SPD							
K68	3	Chen2009b								5.7	896.7	0.761	**3.88**							FTO		Ac, Hel., Et, UV-O_3	TiO_2		100	SPD	30	DB	500 (450)	0.5	20	RT	12	TiO_2 from Showa
N719	10	Howie2007						0.25												FTO	15		TiO_2	2-3	yes	SPD	9		550					
N719	10	Howie2007																																
D21L6	33	Yum2009	3.70E+04	458	Et.	0.98V vs.NHE	-1.35V vs.NHE		99.52 % sun	9.64	798	0.57	**4.44**	54	460								TiO_2	1.7			20							
N719		This work						0.07	100 mW/cm²	0.13 (1.43 at -1 V)	510	0.12	**0.008**					7 months old, kink		FTO	10	Deconex, Et, 1h 500 °C	TiO_2	ca. 3	25	ALD	13	DB	500	2	-	-	-	+ 1 h at 500 °C in O2
I		This work	4E+05	432	THF	-5.2 (J-agg.)	-3.2 (J-agg.)	0.07	100 mW/cm²	0.08 (0.54 at -1 V)	370	0.20	**0.006**					coarse-porous cell, 7 months old, kink		FTO	10	Deconex, Et, 1h 500 °C	TiO_2	ca. 3	25	ALD	ca. 200	DB	500	1	50	80	3	+ 1 h at 500 °C in O2
D5	8	Hagberg2008							99 % sun	6.31	865	0.57	**3.11**			90	60	1000		FTO	15	Hel, Ac, Et	TiO_2	1.7	100	SPD	20	DB	500	0.5	20		o.n.	annealed in O_2
D7	8	Hagberg2008							99 % sun	5.02	785	0.71	**2.79**			90	60	1000		FTO	15	Hel, Ac, Et	TiO_2	1.7	100	SPD	20	DB	500	0.5	20		o.n.	annealed in O_2
D9	8	Hagberg2008							99 % sun	7.72	756	0.56	**3.25**			90	60	1000		FTO	15	Hel, Ac, Et	TiO_2	1.7	100	SPD	20	DB	500	0.5	20		o.n.	annealed in O_2
D11	8	Hagberg2008							99 % sun	5.85	811	0.63	**3.01**			90	60	1000		FTO	15	Hel, Ac, Et	TiO_2	1.7	100	SPD	20	DB	500	0.5	20		o.n.	annealed in O_2
D9	8	Hagberg2008							9.2 % sun				**3.5**	40-50	420-530					FTO	15	Hel, Ac, Et	TiO_2	1.7	100	SPD	20	DB	500	0.5	20		o.n.	annealed in O_2
C201	32	Wang2008	4.12E+04	514	chloroform	1.0 vs. NHE	(-0.78) --> -0.87 vs. NHE		100 mW/cm²	9.06	860	0.61	**4.8**							FTO			TiO_2	1.7	yes	SPD	20	DB	500		20		o.n.	after TiCl4: 450 °C
Z907	7	Fabregat-Santiago2009																																

Abbreviations of methods:

AA	acetic acid	RT	room temperature
appl.	application	SC	spin coated
CP	compressed	SP	screen printing
DB	doctor bladed	SPD	spray pyrolysis deposition
det.	detergent	SPD-O_2	SPD with O_2 as carrier gas
disp.	dispergent	sput.	sputtered
Et	ethanol	TCO	transparent conductive oxide
EC	ethyl cellulose	th.	thickness
evap.	evaporated	terp.	terpineol
Hel.	Helmanex detergent	UB	ultrasonic bath
IL	ionic liquid	UV-O_3	UV-ozone
Me.	methanol		
o. n.	over night		
O_2	in O_2 atmosphere		
O_2-pl.	O_2-plasma		

Abbreviations of compounds:

AN	acetonitrile
AZO	Al:ZnO
bmii	butylmethyl imidazolium iodide
BN	Benzonitrile
Bu_4N	tetrabutyl-ammonium
CB	Chlorobenzene
D102	Indoline dye
D149	Indoline dye
dmii	1,3-dimethyl-3-imidazolium iodide
dmpii	1,2-dimethyl-3-propylimidazolium iodide
$EMIB(CN)_4$	1-ethyl-3methyl-imidazolium tetracyanoborate
emii	1-ethyl-3-methyl-imidazolium iodide
FTO	F:SnO_2
GBA	4-guanidinobutyric acid from Fluka
GuNCS	guanidinium thiocyanate (gtc)
H2PtCl6	hexachloroplatinic acid
HDMA	hexadecylmalonic acid
ITO	Sn:In_2O_3
J-agg.	J-aggregate
K68	Ru-thiocyanato-bipyridyl complex
Li triflate	Lithium trifluoromethanesulfonate
mbii	*N*-methyl-*N*-butyl imidazolium iodide
MP	1-methoxy-2-propanol
MPN	3MPN, 3-Methoxypropionitrile
N3	Ru-thiocyanato-bipyridyl complex
N621	Ru-thiocyanato-bipyridyl complex
N719	Ru-TBA-thiocyanato-bipyridyl complex
N749	Ru-thiocyanato-terpyridyl complex
NBB	*N*-butyl benzimidazole
NKX-2311	Coumarine dye
NMBI	*N*-Methylbenzimidazole
PEG	Polyethylene glycol
pmii	1-propyl-3methylimidazolium iodide
Sb dopant	(tris (4-bromophenyl)ammoniumyl hexachloroantimonate
Spiro-MeOTAD	2,2',7,7'-tetrakis-(*N*,*N*-di-*p*-methoxyphenyl-amine)9,9'-spirobifluorene
t-butanol	*tert*-Butanol
TBAI	Tetrabutylammonium iodide
tBP	4TBP, 4-*tert*-Butylpyridine
TFSI-Li	Bis(trifluoromethane)sulfonimide lithium salt
THF	tetrahydrofuran
VN	valeronitril
Z-907	Ru-thiocyanato-bipyridyl complex
ZnPor	Zinc porphyrin

Dye						Hole transport																			
Staining										Iodine (I_2)	Spiro-MeOTAD	LiI / M	TFSI-Li	TFSI-Li	tBP / M	tBP									
dye-conc. / mM	solvent	time/h	temp./°C	comment		solvent 1	Vol.-%	solvent 2	Vol.-%	/ M	/ M		/ mM	/ mol-% spiro.		/ mol-% spiro.	Add. 1	conc. / M	Add. 2	conc. / M	sealant	cathode	appl.	th. / nm	comment
0.3 + 0.075	AN:*t*-butanol 1:1					MPN	100			0.1							**pmii**	0.6	NMBI	0.45	Bynel hot melt ring, 35 µm thick				heating posttreatment at 55°C for 4 h, electrolyte filled in with vacuum, hole drilled by sand blasting
0.3	AN:*t*-butanol 1:1	12	RT			MPN	100			0.1							**pmii**	0.6	NMBI	0.45	Bynel hot melt ring, 35 µm thick				heating posttreatment at 55°C for 4 h, electrolyte filled in with vacuum, hole drilled by sand blasting
																					35 µm thick Bynel rin	Pt-FTO	0.005 M hexachloroplatinic acid in isopropanol at 400 C for 15 min		
																					35 µm thick Bynel rin	Pt-FTO	0.005 M hexachloroplatinic acid in isopropanol at 400 C for 15 min		
																					35 µm thick Bynel rin	Pt-FTO	0.005 M hexachloroplatinic acid in isopropanol at 400 C for 15 min		
0.3	AN:*t*-butanol 1:1	20-24	RT			MPN	100			0.1							dmpii	0.8	NMBI	0.5	25 µm Surlyn 1702	Pt-FTO	H2PtCl6 in ethanol (2		hole drilled by sand blaster, then cleaned with water in USB, aceton and 0.1 M HCl-aq, after Pt application: 400°C 15 min
						AN	85	VN	15	0.03					0.5		mbii	0.6	GuNCS	0.1	Surlyn 1702	Pt-FTO	H2PtCl6 SC		
						AN	85	VN	15	0.03					0.5		mbii	0.6	GuNCS	0.1	Surlyn 1702	Pt-FTO			
0.5	AN:*t*-butanol 1:1	24				AN	85	VN	15	0.03					0.5		mbii	0.6	GuNCS	0.1	Surlyn 1702	Pt-FTO			
0.3	AN:*t*-butanol 1:1	20-24	RT			MPN	100			0.1							dmpii	0.8	NMBI	0.5	25 µm Surlyn 1702	Pt-FTO	H2PtCl6 in ethanol (2		hole drilled by sand blaster, then cleaned with water in USB, aceton and 0.1 M HCl-aq, after Pt application: 400°C 15 min
0.5	ethanol	12	RT			MPN	100			0.05		0.7			0.055										
0.5	ethanol	12	RT			MPN	100			0.05		0.7			0.5										
0.3	ethanol	1.5	60			MPN	100			0.05		0.1			1		dmpii	0.6							
0.5	ethanol	0.5		desorption in 10 mM KOH		MPN	100			0.05		0.5			0.5						Surlyn	Pt-FTO			
0.3	ethanol	3	80	1h excess-dye desorption																					
0.3	AN:*t*-butanol 1:1	18				AN	100			0.05		0.1			0.5		dmpii	0.6							
0.3	AN:*t*-butanol 1:1	20	RT			AN	50	VN	50	0.05		0.1			0.5		pmii	0.6				Pt-FTO	sputtered		
0.3	AN:*t*-butanol 1:1	o. n.		rinsed with AN		**MPN**	**100**			**0.1**		**0.1**			**0.5**		**TBAI**	**0.6**			Surlyn 1472	Pt-FTO			
						AN	100			0.05		(0.1)			0.5		pmii	0.6	(GuNCS)	(0.1)					Examination the effect of $TiCl_4$ treatment
0.5	AN:*t*-butanol 1:1	17				MPN	100			0.05		0.1			0.6		dmii	0.5				Pt-Ti			
0.5	AN:*t*-butanol 1:1	17				MPN	100			0.05		0.1					dmii	0.5				Pt-Ti			
						MPN	100			0.05		0.1					dmii	0.5				Pt-Ti			
0.3	ethanol	15	RT			AN	85	VN	15	0.04		0.025			0.28		mbii	0.6	GuNCS	0.05					
0.3	ethanol+10 mM C	4	RT			AN	85	VN	15	0.04		0.025			0.28		mbii	0.6	GuNCS	0.05	Surlyn 1702, 25µm D	Pt-FTO			Sealant Bynel used to close the hole, antireflection and UV-cut off-film was attached: ARKTOP from Asahi Glass
0.3	ethanol+10 mM C	4	RT			AN	85	VN	15	0.04		0.025			0.28		mbii	0.6	GuNCS	0.05	Surlyn 1702, 25µm D	Pt-FTO			
0.3	ethanol+10 mM C	4	RT			AN	85	VN	15	0.04		0.025			0.28		mbii	0.6	GuNCS	0.05	Surlyn 1702, 25µm D	Pt-FTO			
0.3	ethanol+10 mM C	4	RT			AN	85	VN	15	0.04		0.025			0.28		mbii	0.6	GuNCS	0.05	Surlyn 1702, 25µm D	Pt-FTO			
0.3	ethanol+10 mM C	4	RT			AN	85	VN	15	0.04		0.025			0.28		mbii	0.6	GuNCS	0.05	Surlyn 1702, 25µm D	Pt-FTO			
0.5	AN:*t*-butanol 1:1	4	RT			AN	85	VN	15	0.05		0.1			0.05		bmii	0.6			Bynel, 35 µm	Pt-FTO			
0.3	sat. acid in CB	5	RT			AN	85	VN	15	0.03		0.05			0.5		dmii	1			25 µm Surlyn	Pt-FTO			hole drilling by an ultrafine sandblaster, vacuum backfilling, Bynel for hole sealing
0.2	ethanol	2																				Pt-FTO			0.05 M hexachloroplatinic acid
						pmii	65	EMIB(CN)$_4$	35	0.2							NBB	0.5	GuNCS	0.1					
0.3	sat. acid in CB	5	RT							1.67%							mixture of: dmii, emii, EMIB(CN)$_4$, NBB, GuNCS				25 µm Surlyn	Pt-FTO			hole drilling by an ultrafine sandblaster, vacuum backfilling, Bynel for hole sealing
	AN					CB	95	AN	5		0.17		50	29.4			Sb dopant	3.30E-04	AN	0.96		Au	evap.	semitransparent	
0.5	AN:*t*-butanol 1:1	8	RT			CB	100				0.17		0.26	0.2	0.18	105.88	Sb dopant	7.60E-04				Au			silver stripes to enhance current collection, sealed with glas and Surlyn and Torr Seal
0.5	AN:*t*-butanol 1:1			Bu_4N, $dcbpyH_2$		CB	100				0.1		27	27.0	0.11	110.00	Sb dopant	2.00E-04	VN	0.11		Au			
0.5	AN:*t*-butanol 1:1			silver nitrate (50 mol-% of d		CB	100				0.1		27	27.0	0.11	110.00	Sb dopant	2.00E-04	VN	0.11		Au			
	ethanol	24		afterw. rinsed w. ethanol		CB	100				0.17		15	8.8	0.11	64.71	-					Au			
0.2	THF	o. n.				CB	100				0.17	Li triflate:	13	7.6	0.13	76.47	Sb dopant	3.00E-04				Au		30	Li triflate inst. Li salt
0.2	THF	o. n.				CB	100				0.17	Li triflate:	13	7.6	0.13	76.47	Sb dopant	3.00E-04				Au		30	Li triflate inst. Li salt
0.5	AN:*t*-butanol 1:1	1				CB	100						yes		yes		Sb dopant	yes				Au	evap.	30	1 min penetration of Spiro-solution, dried for 30 min in Ar-flow and evacuated at ~5x10^{-6} mbar
0.3	AN:*t*-butanol 1:1										yes		yes		yes		Sb dopant	yes				Au	evap.	30	
0.3	AN:*t*-butanol 1:1			silver nitrate							yes		yes		yes		Sb dopant					Au	evap.	30	
0.3	**AN:*t*-butanol 1:1**		**RT**			**CB**	**100**				**0.17**		**13**	**7.6**	**0.13**	**76.47**	**Sb dopant**	**3.00E-04**				**Au**	**evap.**	**30**	
						CB	**100**				**0.17**		**13**	**7.6**	**0.11**	**64.71**						**Au**			
6	GBA : MP 1:1	10 min	RT	rinsed with AN		CB	100	(AN)	(1.5)				8.7		0.047							Au	evap.	100	
0.3	AN:*t*-butanol 1:1					CB	100	(AN)	(2.6)		0.15		21.9	14.6	0.12	80.00	Sb dopant	8.60E-03	AN	0.50		Au	evap.	30	evap. at 10^{-6} mbar
0.5	AN:*t*-butanol 1:1					CB	100	(AN)	(1.5)		0.15		8.7	5.8	0.047	31.33			AN	0.29		Au		30	
						CB	100				0.17		19.5	11.5	0.12	70.59						Au	evap.	30	
1	AN:*t*-butanol 1:1	12	RT			CB	100				**0.18**		0.21	0.1	0.11	61.11	Sb dopant	2.60E-04				Au			
															-										
0.3	ethanol	15	RT			CB	100				yes		yes									Au		50	
0.5	AN:t-butanol 1:1	2h	60	rinsed with AN:*t*-butanol		CB	100	(AN)	(2.2)		**0.17**		13	7.6	0.12	80.00	-	-	AN	0.42		Au	sputtered	50	7 months old ss-DSSC (slight degradation) with kink in I-V curve
0.1 (100 µl)	THF	sprayed	RT (110)	*n*-heptane post-treatment		CB	100	(AN)	(2.2)		**0.17**		13	7.6	0.12	80.00	-	-	AN	0.42		Au	sputtered	50	7 months old coarse-porous dye aggregate solar cell (DASC) with kink in I-V curve, *n*-heptane treatment: 4 h at 110°C
		6		rinsed with AN		CB	100						yes		yes							Au		50	Spiro spincoating like Snaith&Grätzel06_2
		6		rinsed with AN		CB	100						yes		yes							Au		50	Spiro spincoating like Snaith&Grätzel06_2
		6		rinsed with AN		CB	100				2.55		yes		yes							Au		50	Spiro spincoating like Snaith&Grätzel06_2
		6		rinsed with AN		CB	100						yes		yes							Au		50	Spiro spincoating like Snaith&Grätzel06_2
		6		rinsed with AN		CB	100						yes		yes							Au		50	Spiro spincoating like Snaith&Grätzel06_2
0.3	sat. acid in CB	5	RT			CB	100				0.17		0.21	0.1	0.00011 ?	0.06						Au		50	Spiro spincoating after 1 min. of penetrating
											0.17		13	7.6	0.11	64.71									

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